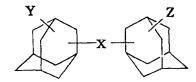
Atty. Dkt. No.: 025311-0107

## **ABSTRACT**

A resist composition comprises: at least one type of a first compound having two or more intramolecular adamantyl structures represented by the chemical formula 1 below; a base resin; and a second compound which generates an acid by active beam irradiation.

## [Chemical formula 1]



wherein X is  $-(OCO)_m-(CH_2)_n-(COO)_m$ , where m=0 or 1 and n=0,1,2 or 3 provided when n=0, m=0; and Y and Z are H, OH, F, Cl, Br, R or COOR, where Y may be Z, or Y and Z may be introduced in a single adamantyl structure and R represents a straight or branched alkyl group having 1 to 8 carbon atoms.